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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/721,657	11/25/2003	Siddhartha Panda	FIS920030133US1	7420
28264 7590 02/05/2007 BOND, SCHOENECK & KING, PLLC			EXAMINER	
ONE LINCOL	N CENTER		VINH, LAN  ART UNIT PAPER NUMBER  1765	
SYRACUSE,	NY 13202-1355			
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SHORTENED STATUTO	RY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MC	ONTHS	02/05/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

Office Action Summary		Application No.	Applicant(s)	Ü			
		10/721,657	PANDA ET AL.				
		Examiner	Art Unit				
		Lan Vinh	1765				
 Period for	The MAILING DATE of this communication app Reply	ears on the cover sheet with the c	orrespondence address				
THE M - Extension - Extension - If the p - If NO p - Failure Any rep	RTENED STATUTORY PERIOD FOR REPLY AILING DATE OF THIS COMMUNICATION. ions of time may be available under the provisions of 37 CFR 1.13 (X (6) MONTHS from the mailing date of this communication. eriod for reply specified above is less than thirty (30) days, a reply eriod for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, oly received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed  s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status							
1)⊠ F	Responsive to communication(s) filed on <u>09 No</u>	ovember 2006.					
	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.						
3)□ S	) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
C	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Dispositio	n of Claims						
5)□ C 6)図 C 7)□ C	Claim(s) <u>1-17</u> is/are pending in the application.  a) Of the above claim(s) <u>1-10</u> is/are withdrawn  Claim(s) is/are allowed.  Claim(s) <u>11-17</u> is/are rejected.  Claim(s) is/are objected to.  Claim(s) are subject to restriction and/or	from consideration.					
Applicatio	n Papers						
9) <u></u> ⊤ا	he specification is objected to by the Examine	r.	•				
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
A	applicant may not request that any objection to the o	drawing(s) be held in abeyance. See	∋ 37 CFR 1.85(a).				
· F	Replacement drawing sheet(s) including the correcti	on is required if the drawing(s) is obj	jected to. See 37 CFR 1.121(d).				
11) T	he oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.				
Priority un	der 35 U.S.C. § 119						
a)	cknowledgment is made of a claim for foreign  All b) Some * c) None of:  Certified copies of the priority documents  Certified copies of the priority documents  Copies of the certified copies of the prior application from the International Bureau e the attached detailed Office action for a list of	s have been received. s have been received in Application ity documents have been received (PCT Rule 17.2(a)).	on No ed in this National Stage				
Attachment(s	s)						
	of References Cited (PTO-892)	4) Interview Summary	· ·				
3) Informa	of Draftsperson's Patent Drawing Review (PTO-948) Ition Disclosure Statement(s) (PTO-1449 or PTO/SB/08) No(s)/Mail Date	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate ratent Application (PTO-152)				

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#### **DETAILED ACTION**

## Response to Arguments

1. Applicant's arguments, see pages 2-5 of the response, filed 11/9/2006, with respect to the rejection(s) of claim(s) 11-15 under 35 U.S.C 102(e) based on Canteloup (296) have been fully considered and are persuasive. Therefore, the rejection has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made in view of Baselmans et al (US 6,809,797)

#### Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 11-15 are rejected under 35 U.S.C. 102(e) as being anticipated by Baselmans et al (US 6,809,797)

Baselmanns discloses a method and apparatus for providing compensation to correct lithography error. The apparatus comprises a transmissive mask MA/filter, the MA/filter having a peripheral region/first region having the beam PB passed through/first transmittance (one beam passes through lens PL) (col 8, lines 9-40; fig. 1-2), a center/second region having the beam PB passed through/second transmittance (two

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beams pass through lens PL) is different from the transmittance at the peripheral region/first region (fig. 2)

Regarding claim 14, fig. 1 of Baselmans shows that the mask MA/filter having the peripheral/first region and center/second region located around a center which reads on the first region and second region are eccentric

Regarding claim 15, since Baselmans discloses the same filter having the same first and second regions for transmittance as the claimed filter under the principle of inherency, positioning Baselmans second region would have inherently reduced transmission in areas where said plasma etching process experiences magnetic filed cusping. It is noted that the claim language of "to reduce transmission in areas where said plasma etching process experiences magnetic filed cusping" is functional claim language. APPARATUS CLAIMS MUST BE STRUCTURALLY DISTINGUISHABLE FROM THE PRIOR ART

>While features of an apparatus may be recited either structurally or functionally, claims< directed to >an< apparatus must be distinguished from the prior art in terms of structurerather than function. >In re Schreiber, 128 F.3d 1473, 1477-78, 44 USPQ2d 1429, 1431-32 (Fed. Cir. 1997) (The absence of a disclosure in a prior art reference relating to function did not defeat the Board's finding of anticipation of claimed apparatus because the limitations at issue were found to be inherent in the prior art reference); see also In regarding claim Swinehart, 439 F.2d 210, 212-13, 169 USPQ 226, 228-29 (CCPA 1971);< In regarding claim Danly, 263 F.2d 844, 847, 120 USPQ 528, 531 (CCPA 1959). "[A]pparatus claims cover what a device is, not what a device

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does." Hewlett-Packard Co. v. Bausch & Lomb Inc., 909 F.2d 1464, 1469, 15 USPQ2d 1525, 1528 (Fed. Cir. 1990) (emphasis in original)

### Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 16-17 rejected under 35 U.S.C. 103(a) as being unpatentable over Baselmans et al (US 6,809,797) in view of Mathies et al (US 6,867,420)

Baselmans filter has been described above. Unlike the instant claimed inventions as per claims 16-17, Baselmans fails to disclose that the filter comprises optical quality glass having a layer of metallic coating of a predetermined thickness, the thickness of said layer of metallic coating varies from the first to the second region although Baselamns discloses that the beam passing through the mask MA/filter

Mathies discloses an optical system comprises a optical interference filter 22, the filter is formed by depositing TiO/metallic coating layer 32 of selected thickness on a quarts or glass substrate (col 3, lines 57-61)

Thus, one skilled in the art at the time the invention was made would have found it obvious to modify Baselmans filter by using a filter comprising optical quality glass having a layer of metallic coating of a predetermined thickness to form a metal light

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shield in order to minimize the effect of laser scattered light as taught by Mathies (col 4, lines 45-52)

#### Conclusion

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Lan Vinh whose telephone number is 571 272 1471. The examiner can normally be reached on M-F 8:30-5:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nadine Norton can be reached on 571 272 1465. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

January 30, 2007